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Role of complexing ligands in trivalent chromium electrodeposition

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1. Introduction

Electroplating technology is widely used in industry and daily life for decoration, anti-corrosion, anti-wear and preparation of metal electrodes [1–3]. Many metals can be electrodeposited from aqueous solutions. In order to obtain high-quality deposits, all kinds of complexing ligands are added into electrolytes. With respect to the Cu, Pb, Zn, Ag, Au, Cd, Pt, Rh, In and Pd plating processes, the complexing ligands, such as CN⁻, sulfamic acid, NH₃ etc. are used to decrease the deposition rate to produce the bright, compact and smooth deposits. While in the cases of Ni, Co and Fe plating processes, the high-quality deposits can be obtained by adding some brighteners instead of complexing ligands. Comparatively, Cr plating process is more complex. Conventional Cr plating is carried out in the hexavalent Cr electrolytes with small amount of H₂SO₄ or fluoride as catalysts. Due to the toxicity of Cr(VI), now this process is strictly restricted in US, Japan, China, Europe and other areas. Recently, trivalent Cr plating is considered as a promising technology to replace the conventional hexavalent Cr plating. In this plating process, the complexing ligands are also added to the electrolytes, whereas they are used to accelerate the deposition of Cr but not to decelerate it [4,5]. Although complexing ligands obviously promote the electroreduction of Cr(III), they also bring some demerits to the trivalent Cr plating process. For example, thick Cr coating with acceptable quality is hardly obtained from this electrolyte; thus, it is only commercially used for decorative thin Cr electroplating. Nevertheless, the decorative thin Cr coating from trivalent Cr is darker than that from hexavalent Cr, which is unfavorable to the commercial decoration.

ABSTRACT

In this study, the Cr(III)-formate, Cr(III)-oxalate and Cr(III)-glycine electrolytes are used as sources for electrodepositing the Cr coatings. The deposition rate and brightness range of the electroplating process in these electrolytes are investigated. The geometric structures of the Cr complex ions are optimized, using density functional theory with General Gradient Approximation/Perdew-Wang 91 (GGA/PW91) calculation. It is found that the deposition rate and brightness range significantly depend on the geometric structure of the Cr(III)-ligand complex ions. The expansion of the distance between Cr and H₂O induced by the introduced complexing ligand is a necessary condition for the electrophating reduction of Cr(III) to metal Cr. The dehydration rate of Cr(III)-ligand complex ions determines the electroplating characteristics of electrolytes. © 2011 Elsevier B.V. All rights reserved.

Some previous researchers [6,7] tried to investigate the effect of complexing ligands on the characteristics of trivalent Cr plating process in order to improve the trivalent Cr plating technology. But heretofore there are no ultimate opinions on the role of complexing ligands in trivalent Cr plating process because few studies have been conducted at molecular level to explore the essential role of complexing ligands in the electroreduction process of Cr(III).

Generally, in aqueous solution metal ions exist in the form of metal- H_2O complex ions. The electroreduction reaction of metal- H_2O complex ions in aqueous solution can be considered as a special nucleophilic substitution reaction that electron replaces H_2O molecule in aqua metal ions. Electron is a special substituent because it is chained to the cathode. Thus, the geometric structure of metal- H_2O complex ions plays an important role in the electroreduction. It is a prerequisite for the electroreduction of metal- H_2O complex ions that metal ions contact the cathodic electrons.

Table 1 summarizes the amount of H_2O molecules (*n*) and the distance between metal ion and $H_2O(r)$ in different metal- H_2O complex ions [8]. Ag and Cu can be electroreduced easily from trimolecular structural $[Ag(H_2O)_2]^{2+}$ and $[Cu(H_2O)_2]^{2+}$ because metal ions can access and contact the cathode easily. Other metal-6H₂O complex ions holding the regular octahedron structure with metal ion as a center and H₂O molecules as vertexes can be divided into two groups. Metal-6H₂O complex ions with *r* larger than 2.04 Å such as $[Ni(H_2O)_6]^{2+}$, $[Co(H_2O)_6]^{2+}$, $[Fe(H_2O)_6]^{2+}$ etc. can be electroreduced easily; and those with *r* smaller than 2.04 Å such as $[AI(H_2O)_6]^{3+}$, $[Cr(H_2O)_6]^{3+}$, $[Fe(H_2O)_6]^{3+}$ etc. can hardly be electroreduced. In fact, metal ions surrounded by six H_2O molecules cannot contact the cathodic electrons unless H₂O molecules depart from them firstly. Under the pull of cathodic electrons, metal-6H₂O complex ions in the former group lose H₂O molecules firstly to expose metal ions, which is propitious to metal ions that contact the cathode to react with

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Amount of H_2O molecules (*n*) and average distance between metal ion and H_2O molecule (a-*r*).

Metal ion	Al ³⁺	Cr ³⁺	Fe ³⁺	Ni ²⁺	C0 ²⁺	Zn ²⁺	Fe ²⁺	In ³⁺	Mn ²⁺	Cd ²⁺	Ag^+	Cu ²⁺
n	6	6	6	6	6	6	6	6	6	6	2	2
r (Å)	1.90	2.00	2.00	2.04	2.08	2.08	2.12	2.15	2.20	2.31	2.41	2.43

cathodic electrons. On the other hand, with respect to metal- $6H_2O$ complex ions in the latter group, the dehydration can hardly occur, and metal ions are unable to contact cathode to react with cathodic electrons. It should be pointed out that Al can be electrodeposited from ionic liquids based on AlCl₃ and organic halide [9] because no $[Al(H_2O)_6]^{3+}$ ions are formed in ionic liquid electrolytes. Thus, it can be confirmed that the dehydration is a necessary condition for the electroreduction of metal- $6H_2O$ complex ions. And the distance between metal ion and H_2O of metal- H_2O complex ions determines their ability to lose H_2O molecules.

It is important to note that the electroreduction of Cr(III) is special in respect that Cr can deposited from $[Cr(H_2O)_{6-x}L_x]^{3-x}$ (L, complexing ligand) rather than $[Cr(H_2O)_6]^{3+}$. Thus, the investigation on the role of geometric structure in the electroreduction of Cr complex ions is important both for the improvement in trivalent Cr electroplating and for the development in theory of metal ions electrodeposition in aqueous solution.

J. Szynkarczuk et al. [10,11] have studied the electrochemical behaviors of trivalent Cr in the presence of formic acid. They thought the electroreduction of Cr complex ions underwent two electrodic processes. The first one is responsible for electroreduction to bivalence Cr when the other to metallic chromium, whereas they did not elucidate the essential role of formic acid during the electroreduction. In our previous work [4], we have investigated the effects of formate on the electroreduction of trivalent Cr by analyzing the geometric structures of the Cr(III)-ligand complex ions. It is found that the formate replaces H₂O molecule in $Cr(H_2O)^{3+}$ to expand the distance between Cr^{3+} and H_2O , which expedite the dehydration to accelerate the electroreduction of trivalent Cr to bivalence Cr. When Cr³⁺ ion obtains an electron, the Cr complex ion becomes $[Cr(H_2O)_4CHOO]^+$ which exhibits a very large r value. In this case, all H₂O molecules are easy to depart from central Cr²⁺ and the further electroreduction of Cr^{2+} will proceed quickly. Nevertheless, there are still some essential issues which are valuable to be further discussed. For example, are the effects of ligand on the electroreduction of Cr(III) in other trivalent Cr electrolytes such as Cr(III)-oxalate and Cr(III)-glycine systems also attributed to the change in the geometric structures? Why do the properties of ligands and molar ratio of Cr to ligand affect the electroplating characteristics of electrolytes? And why can the thick Cr coatings with acceptable quality hardly be obtained from Cr(III)-formate electrolyte in the commercial operation?

In this work, we investigate the equilibrium geometric structures of Cr(III)-ligand complex ions, brightness range and deposition rate in three different electrolyte systems. Cr(III)-formate, Cr(III)-oxalate and Cr(III)-glycine electrolyte systems are selected because they are popularly used both for academic research and for commercial

Table 2	
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Component of electrolytes.

operation. The final aim is to establish a systemic theory of trivalent Cr electroplating, which may provide some valuable information both for trivalent Cr electroplating and for the electrodeposition of other metal from aqueous solutions.

2. Experimental

2.1. Bright range measurement

The chemical components of electrolytes are summarized in Table 2. Electrolytes were boiled for 1 h in order to promote the ions reach equilibrium state, and then NaOH solution was used to adjust pH value to 3.0. To achieve the final thermodynamic equilibrium state, the solutions were placed for 30 days before the electrodeposition. The final pH value of solutions needs to be adjusted to 3.0 in order to ensure the accuracy of following measured results. "Hull cell" of 267 ml was used as the plating bath, dimensionally stable titanium plate (Xinxiang Future Hydrochemistry Co., China) and copper were used as the anode and cathode, respectively, and the electrodeposition was conducted with the current of 6 A at 30 °C for 2 min. The length of bright Cr-covered area was measured to determine the bright range. The corresponding current density was evaluated by the experimental equation (German Criterion DIN50957) expressed as

D = I(510.19 - 524.01 lgL / 10)

where *I* is the total current density in A m⁻², *D* is the current density at the certain position (A), and *L* is the distance between A and the edge of the cathodic copper in mm.

2.2. Deposition rate test

Copper substrate with areas of 0.04 dm² was used as cathode. In order to obtain the even coating on the substrate, the electrodeposition was carried out in the bath of 5000 ml with graphite plate as the cathode. The deposition rate was determined by measuring the quality difference between coating-covered substrate and blank substrate.

2.3. Geometric structure analysis

Geometric structural conversion of Cr complex ions in electrolytes was analyzed by means of GGA/PW91 calculation which is widely used for optimizing the geometric structure of compounds [12,13].

3. Results and discussion

Fig. 1 shows the bright range of the copper after "Hull cell" experiment in different electrolytes. Bright Cr coatings are obtained in the Cr(III)-formate electrolytes with the current density ranging from $4 \text{ A } \text{dm}^{-2}$ to 57 A dm⁻². And it seems that the molar ratio of Cr to formate does not affect the bright range. Comparatively, the bright range is significantly affected by the molar ratios of Cr to oxalate and Cr to glycine. The bright range is from 10 A dm⁻² to 60.5 A dm⁻² for

Reagent	1) Cr-formate $(1:1) \text{ mol } l^{-1}$	2) Cr-formate (1:2) mol l^{-1}	3) Cr-oxalate (1:1) mol l ⁻¹	4) Cr-oxalate (1:2) mol l^{-1}	5) Cr-glycine $(1:1) \text{ mol } l^{-1}$	6) Cr-glycine (1:2) mol l^{-1}
Cr ³⁺	0.6	0.6	0.6	0.6	0.6	0.6
NaCl	1	1	1	1	1	1
НСООН	0.6	1.2				
НООСООН			0.6	1.2		
H ₂ NCH ₂ COOH					0.6	1.2
AlCl ₃	0.5	0.5	0.5	0.5	0.5	0.5

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